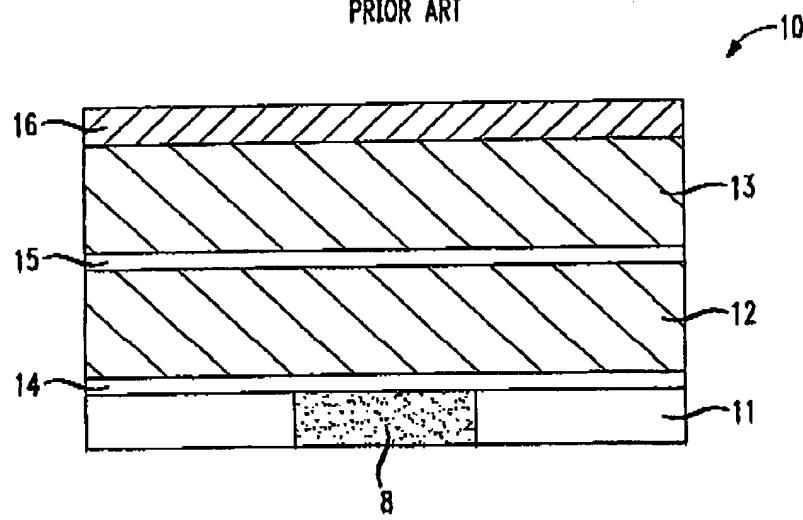


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 Robert L. Walter (407-926-7700)  
 Serial #10/026,257

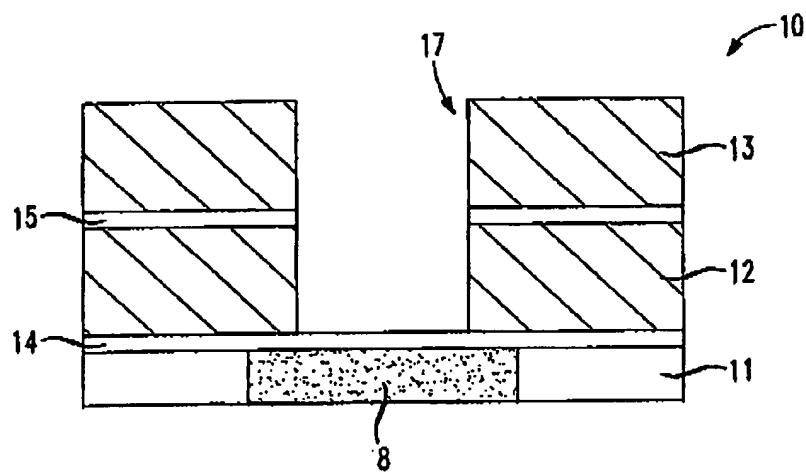
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**FIG. 1**  
**PRIOR ART**



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**FIG. 2**  
**PRIOR ART**



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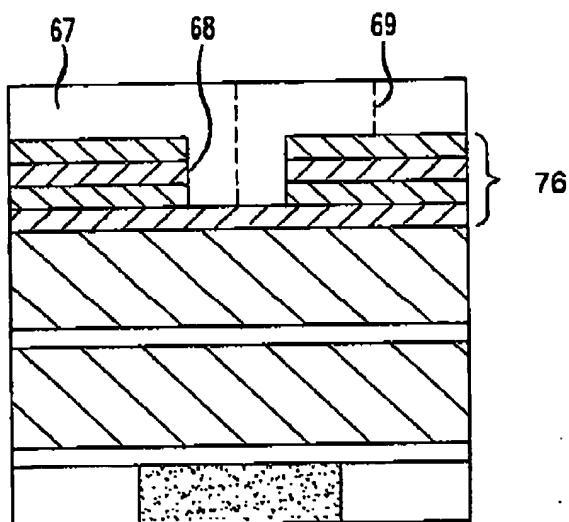
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FIG. 27



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FIG. 28

